

Attorney's Docket No. 5470.285DV

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: DeSimone et al.

Serial No.: To be assigned

Filed: Concurrently herewith

For: METHODS OF FORMING POLYMERIC STRUCTURES USING CARBON  
DIOXIDE AND POLYMERIC STRUCTURES FORMED THEREBY

Date: February 23, 2004

Mail Stop Patent Application

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

**INFORMATION DISCLOSURE STATEMENT  
CITATION UNDER 37 C.F.R. § 1.97**

Sir:

Attached is a list of documents on forms PTO-1449.. All items listed on the PTO-1449s were cited in parent application Serial No. 10/109,588, filed March 28, 2002. Since the benefit of this application is claimed under 35 U.S.C. §120, no other copies need to be furnished in accordance with 37 C.F.R. §1.98(d); however, copies will be furnished on request. It is requested that these documents be considered by the Examiner and officially made of record in accordance with the provisions of 37 C.F.R. §1.97 and Section 609 of the MPEP.

Respectfully submitted,



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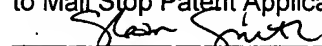
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Sloan Smith

# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)



Application Number	10/400,588 — To Be Assigned
Filing Date	March 28, 2002
First Named Inventor	Joseph M. DeSimone
Group Art Unit	1772
Examiner Name	Unknown
Attorney Docket Number	5470.351DV

## U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.	U.S. Patent Document	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code (if known)		
	1	US 2002/0020946 A1	Hirakoa et al.	02/21/2002	
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## FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No.	Foreign Patent Document	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T
		Office	Number	Kind Code (if known)		

## OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T
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	21	Olmsted, Peter D., et al., <i>Strong-Segregation Theory of Bicontinuous Phases in Block Copolymers</i> , <i>Physical Review Letters</i> , Vol. 72, No. 6, pp. 936-941 (7 February 1994)	
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Examiner Signature	<i>John F. Loe</i>	Date Considered	5/03
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